

**IN THE CLAIMS:**

Please amend claim 22 as follows:

22. (Amended) A method of spin-coating a semiconductor substrate, comprising the steps of:

- (a) dropping coating material onto a semiconductor substrate;
- (b) rotating said semiconductor substrate about a center thereof; and
- (c) generating an electric field circumferentially around said semiconductor substrate and said coating material, said electric field having an electric polarity opposite to an electric polarity of said coating material.